

**IN THE CLAIMS:**

Please amend claims as follows:

1. (Currently Amended) A platen for supporting ~~the a~~ polishing material in a chemical mechanical polishing system, comprising:  
~~a body having an upper support surface adapted to support a the polishing material during processing; and, wherein the upper support surface is a substantially rigid and non-planar upper support surface defining an upper surface of the body for supporting the polishing material and the upper support surface has no planar portion.~~
2. (Original) The platen of claim 1, wherein the upper support surface is concave.
3. (Withdrawn) The platen of claim 1, wherein the upper support surface is convex.
4. (Withdrawn) The platen of claim 1, wherein the upper support surface includes both convex and concave portions.
5. (Withdrawn) The platen of claim 1, wherein the upper support surface includes an inner region and at least one outer region, wherein the inner region and outer region are at different elevations.
6. (Withdrawn) The platen of claim 1, wherein the body is rotatable.
7. (Withdrawn) The platen of claim 1, wherein the body is fixed.
8. (Currently Amended) The platen of claim 1, wherein the upper support surface of the body is textured patterned.

9. (Currently Amended) The platen of claim 8, wherein the texture patterned upper support surface ~~further comprises:~~ is produced by a plurality of grooves formed in the upper support surface of the body.

10. (Currently Amended) The platen of claim 1, wherein the upper support surface of the body ~~further comprises:~~ has one or more raised portions ~~on the upper~~ surface defining a mounting surface[[;]] and a recessed area ~~defined by the one or more~~ raised portions.

11. (Withdrawn) The platen of claim 1, wherein the body further comprises: magnetic device for coupling the polishing material to the upper surface.

12. (Withdrawn) The platen of claim 11, wherein the magnetic device further comprises:

at least one of a magnetic or electromagnet.

13. (Withdrawn) The platen of claim 12 further comprising:  
a magnetically couplable material coupled, embedded or fixed to the polishing material.

14. (Withdrawn) The platen of claim 1, wherein the body further comprises:  
vacuum port open to the upper surface.

15. (Withdrawn) The platen of claim 1, wherein the body further comprises:  
polishing fluid delivery port open to the upper surface.

16. (Currently Amended) A platen for supporting the a polishing material in a chemical mechanical polishing system, comprising:  
a body adapted to support a the polishing material during processing[[;]], wherein the body has a substantially rigid non-planar upper support surface defining an upper support surface ~~of the body~~ for supporting the polishing material[[;]], and a plurality of

recesses formed in the upper support surface, wherein the upper support surface has no planar portion.

17. (Original) The platen of claim 16, wherein the recesses are grooves.

18. (Withdrawn) The platen of claim 17, wherein the upper support surface has at area having a concave cross section.

19. (Currently Amended) A chemical mechanical polishing system comprising:  
a platen having a non-planar, substantially rigid upper support surface, wherein the upper support surface has no planar portion;  
a polishing material disposed on the upper support surface; and  
a polishing head adapted to retain a substrate against a working portion of the polishing material during processing.

20. (Currently Amended) The chemical mechanical polishing system of claim 19, wherein the upper support surface further comprises has:

at least one recessed area formed therein[[:]], and  
at least one area projecting above the recessed are area and defining the non-planar upper support surface.

21. (Currently Amended) The chemical mechanical polishing system of claim 19, wherein a distance between the upper support surface and a plane defined by a lower surface of the polishing head is not uniform[[:]].